Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
Li.	4455	(mask same writ\$4) and (design same data)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/20 15:34
L2	. 232	(mask same writ\$4) and (design same data) and layer and opc	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/20 15:34
L3	173	(mask same writ\$4) and (design same data) and layer and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/20 15:34
L4	301	(mask same writ\$4) and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/20 15:34
L5	152	(mask same writ\$4) and opc and print and ("716"/\$:ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOGR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/20 15:34
L6	132	(mask near6 writ\$4) and opc and print and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/20 15:34
L7	1133	(mask near6 writ\$4) and ("716"/\$. ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/20 15:34
L8	75	(mask same writ\$4) and (design same data) and layer and opc and feature and context	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/20 15:34

L9	29	(mask same writ\$4) and (design same data) and (multiple same layer) and print and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/20 15:34
L10	56	(mask near6 writ\$4) and (multiple same layer) and print\$4 and opc and ("716"/\$.ccls. or "430"/\$.ccls. )	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/20 15:34
L11	47	(mask same writ\$4) and (design same data) and (multiple same layer) and print\$4 and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/20 15:34
L12	54	(mask same writ\$4) and (design same data) and (multiple same layer) and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/20 15:34
L13	127	(mask near6 writ\$4) and opc and print and layer and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/20 15:34
L14	235	(mask near6 writ\$4) and opc and layer and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ÖN	2006/02/20 15:34
L15	77	(mask near5 lithography) and (design same data) and (multiple same layer) and opc and ("716"/\$. ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/20 15:34
L16	9	(mask near5 lithography) and (design same data) and tag and opc and ("716"/\$.ccls. or "430"/\$. ccls.)	US-PGPUB; USPAT; USOGR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/20 15:34

L17	10	(mask same lithography) and (design same data) and tag and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/20 15:34
L18	11	(mask same lithograph\$3) and (design same data) and tag and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/20 15:34
L19	9	(mask near5 lithography) and (design same data) and tag and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/20 15:34
L20	37	(mask near5 lithography) and (design same data) and (multiple same layer) and opc and writ\$3 and ("716"/\$.ccls. or "430"/\$.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/20 15:34
L21	34	(mask near6 writ\$4) and (multiple same layer) and print and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/20 15:34
L22	34	(mask near6 writ\$4) and (multiple same layer) and print and writ\$3 and opc and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/20 15:41
L23	4434	mask near4 inspect\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/20 15:41
L24	325	(mask near4 inspect\$4) and opc	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/20 15:42

L25	277	(mask near4 inspect\$4) and opc and layer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/20 15:42
L26	201	(mask near4 inspect\$4) and opc and layer and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/20 15:43
L27	90	(mask near4 inspect\$4) and opc and layer and relation\$6 and ("716"/\$.ccls. or "430"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/20 16:04
L30	69	(mask near4 inspect\$4) and opc and layer and relation\$6 and feature and lithography and wafer and ("716"/\$.ccls. or "430"/\$.ccls. )	US-PGPUB; USPAT; USOGR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/02/20 16:12

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